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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

CHO ET AL.

Atty. Ref.: ARC-4105-73

Serial No. 10/568,770

TC/A.U.: 1795

Filed: March 21, 2006

Examiner: Smith

For: FERROELECTRIC THIN-FILM PRODUCTION METHOD,
VOLTAGE-APPLICATION ETCHING APPARATUS, FERROELECTRIC
CRYSTAL THIN-FILM SUBSTRATE, AND FERROELECTRIC CRYSTAL
WAFER

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March 9, 2009

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

Attention is invited to the attached copy of a European Search Report mailed February 10, 2009 in the counterpart European application and a copy of each non-U.S. patent document cited in it. U.S. family members of the EP references are also listed. A completed Form PTO/SB/08A is also attached.

Official citation and consideration of all the listed documents is requested. Please return to the undersigned a copy of the attached PTO/SB/08A with the examiner's initials in the left column [MPEP §609] with the next communication.

I hereby certify that each item of information contained herein was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months ago from the filing date of this statement [see 37 C.F.R. § 1.97(e)(1)].

CHO ET AL.

Serial No. **10/568,770**

The filing of an Information Disclosure Statement shall not be construed as a representation that a search has been made, an admission that the information cited is, or is considered to be, material to patentability [37 C.F.R. § 1.97(g) & (h)] or that no other material information exists.

The Commissioner is hereby authorized to charge our Deposit Account No. 14-1140 for any fees required in connection with the filing of this Information Disclosure Statement.

Respectfully submitted,

NIXON & VANDERHYE P.C.

By: _____



Arthur R. Crawford

Reg. No. 25,327

ARC:eaw
901 North Glebe Road, 11th Floor
Arlington, VA 22203-1808
Telephone: (703) 816-4000
Facsimile: (703) 816-4100